L Number	Hits	Search Text	DB	Time stamp
1	25	((((((magnetic adj head) or (magneto adj	USPAT;	2003/09/03 12:40
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	1
		or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
ļ		(resist or photoresist or imag\$3 or		
		<pre>pattern\$3))) and ((resist or photoresist</pre>		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and (((mill\$3 or ion		1
		adj beam or FIB or RIE or ion adj etch\$3		
		or sputter\$3) or (lift adj off or liftoff		
		or remov\$3 or etchback or etch\$3 adj		
		back)) near5 (resist or photoresist or		1
		imag\$3 or pattern\$3))) and ((heat\$3 or	,	
.1		bak\$3) with (resist or photoresist or		
114	2	imag\$3 or pattern\$3))	USPAT;	2003/09/03 13:05
14	2	(((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or	US-PGPUB;	2003/03/03 13:05
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM TDB	
		or (GMR same magneto\$15)).ti,ab.) and	1011_100	
		(resist or photoresist or photopolymer\$7		İ
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		190
		<pre>pattern\$3))) not (((((magnetic adj head)</pre>		İ
		or (magneto adj resistive) or		
		magnetoresistive or magnetophotoresistive		1
		or (magneto adj photoresistive) or (giant		
		adj magneto\$15) or (GMR same	•	
1		magneto\$15)).ti,ab.) and (resist or		
		photoresist or photopolymer\$7 or		
		photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		1
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and		
		(polymethylglutarimide)		
15	54		USPAT;	2003/09/03 13:20
		(napthoquinonediazide or	US-PGPUB;	
		napthoquinonediazido)	EPO; JPO;	
		• • •	IBM TDB	
16	3	((resist or photoresist) and	USPAT;	2003/09/03 13:25
	_	(napthoquinonediazide or	US-PGPUB;	
		napthoquinonediazido)) and (novolac or	EPO; JPO;	
		novolak) and dissolution near3 accelerat\$3	IBM_TDB	
17	32	((430/314,316,319-320,328-329).ccls. and	USPAT;	2003/09/03 13:27
		((oxygen or "O.sub.2") same ((nitrogen or	US-PGPUB;	
		"N.sub.2") and (hydrogen or "H.sub.2"))	EPO; JPO;	
		same (ash\$3 or etch\$3))) and (heat\$3 or	IBM_TDB	
l l		bak\$3) same (resist or photoresist)		Ī

	1 44-	1 (420 (200 1 - and (b + 62 5- 5- 62)	HCDAM.	2003/00/03 13-31
18	225	(430/328.ccls. and (heat\$3 or bak\$3) same	USPAT;	2003/09/03 13:31
		(expos\$3) same (develop\$3)) not	US-PGPUB;	
		(((430/314,316,319-320,328-329).ccls. and	EPO; JPO;	
		((oxygen or "O.sub.2") same ((nitrogen or	IBM_TDB	
		"N.sub.2") and (hydrogen or "H.sub.2"))		
		same (ash\$3 or etch\$3))) and (heat\$3 or		
		bak\$3) same (resist or photoresist))		
-	22	(("20020042029") or ("6040965") or	USPAT;	2003/03/18 16:46
		("5932396") or ("6480355") or ("5747198")	US-PGPUB	
		or ("6289578") or ("5725997") or		
		("6483664") or ("6501618") or ("6504678")		1
		or ("20010010885") or ("20010019036") or		1
		("20010027029") or ("6465149") or		
i		("20010019465") or ("20010035355") or		
		("20010038517") or ("20010035343") or		
		("20020037476") or ("20020071211") or		
		("20030007295") or ("20020187430")).PN.		
_	61373	((magnetic adj head) or (magneto adj	USPAT;	2003/03/07 17:59
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM TDB	
		or (GMR same magneto\$15)).ti,ab.	_	
_	2793	(((magnetic adj head) or (magneto adj	USPAT;	2003/03/07 18:00
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
ļ		photoresistive) or (giant adj magneto\$15)	IBM TDB	
		or (GMR same magneto\$15)).ti,ab.) and	_	
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)		
_	2003	((((magnetic adj head) or (magneto adj	USPAT;	2003/03/07 19:27
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM TDB	
		or (GMR same magneto\$15)).ti,ab.) and		
<u> </u>		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		1
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3	ľ	
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
	1	pattern\$3))	1	
_	65	(((((magnetic adj head) or (magneto adj	USPAT;	2003/03/07 19:04
_	63	resistive) or magnetoresistive or	US-PGPUB;	2003/03/07 19.04
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	
		or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj	1	
	1	treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same	1	
	[	(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
	1	"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
	F .	or "H.sub.2")))))		

resistive) or magnetoresistive or magnetophotoresistive) or (giant adj magnetosh) or (GMR same magnetosh)). it, ab. and (resist or photoresist or photopolymers? or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrink\$3 or ontract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3))) and ((fuorine or fluoride or "F" or "F. sub.2" or ((nitrogen or "M" or "N. sub.2")) and (shdrogen or "H" or "H. sub.2")))))) and ((mil1\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3)) or (lift adj off or liftoff or remov\$3 or apattern\$3)) and ((heat\$3 or bak\$3)) with (resist or photoresist or imag\$3 or pattern\$3)) and ((heat\$3 or bak\$3)) with (resist or photoresist or imag\$3 or pattern\$3))  56 (((((magnetic adj head) or (magneto adj photoresistive) or (giant adj magneto\$15)) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist) or into photoresist or photoresist or photoresist or photoresist or into photoresist or photoresist or into photoresist or photoresist or into photoresist or photoresist or imag\$3 or pattern\$3) and ((resist or photoresist or photoresist or imag\$3 or pattern\$3) and (resist or photoresist or "N" or "N. sub.2") and (hydrogen or "H" or "H. sub.2") and hydrogen or "H" or "H. sub.2") and hydrogen or "H" or "H. sub.2")					
magnetophotoresistive or (magneto adj photoresistive) or (gant adj magneto\$15) or (GMR same magneto\$15)).ti, ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash ad)) treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrink\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3)) and ((resist or photoresist or imag\$3 or pattern\$3)) and ((mil1\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) neaf5 (resist or photoresist or imag\$3 or pattern\$3)) and ((mil1\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or bak\$3) with (resist or photoresist or imag\$3 or pattern\$3)) and ((heat\$3 or bak\$3) with (resist or photoresist or imag\$3 or pattern\$3)) and ((heat\$3 or bak\$3) with (resist or photoresist or magneto adj resistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrink\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or photoresist or imag\$3 or pattern\$3)) and ((resist or photoresist or imag\$3 or pattern\$3) and (loresist or photoresist or """ or """ or "", sub.2") and (hydrogen or """ or "", sub.2") and (hydrogen or """ or "", sub.2") and (hydrogen or """ or "", sub.2") and hydrogen or """ or "", sub.2") and hydrogen or """ or "", sub.2") and hydrogen or """ or """ or "", sub.2" or loresist or pho	_	23	((((((magnetic adj head) or (magneto adj	USPAT;	2003/09/03 12:27
photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).it, ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and (fash3 or fash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$7 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and (fresist or photoresist or imag\$3 or pattern\$3) same (foxygen or "0" or "0. sub.2") and (fluorine or fluoride or "F" or "F. sub.2" or (introgen or "N" or "N. sub.2") and (hydrogen or "H" or "H. sub.2"))))) and ((imill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or imag\$3 or pattern\$3))  - (((((magnetic adj head) or (magneto adj resistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresistive or photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and (fash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3)) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "0" or "0.sub.2") and (fluorine or fluoride or "F" or "F. sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))) and ((imill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or			· · · · · · · · · · · · · · ·		
or (GMR same magneto\$15)].ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or nerrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3)) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "0" or "0.sub.2") and (fluorine or fluoride or "F" or "F. sub.2" or ((nitrogen or "N. or "N. sub.2"))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near\$ (resist or photoresist or imag\$3 or pattern\$3))) and ((heat\$3 or bak\$3) with (resist or photoresist or imag\$3 or pattern\$3))) and ((heat\$3 or bak\$3) with (resist or photoresist or imag\$3 or pattern\$3))) (((((magnetic adj head) or (magneto adj photoresistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or photoresist or imag\$3 or pattern\$3)) and ((fuesits or photoresist or imag\$3 or pattern\$3) same ((oxygen or "0" or "0.sub.2") and (fydrogen or "H" or "M.sub.2"))))) and ((finils\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or				i i	
(resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3)) ame ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near\$ (resist or photoresist or imag\$3 or pattern\$3)) and ((heat\$3 or bak\$3) with (resist or photoresist or imag\$3 or pattern\$3)) or ((((((mangetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or reduc\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (flydrogen or "H" or "H.sub.2")))))) and ((fmill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near\$ (resist or photoresist or			photoresistive) or (giant adj magneto\$15)	IBM_TDB	1
or photoimag\$5) and ((ash\$3 or (ash adj treāt\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrink\$3 or shrink\$3 or shrink\$3 or or shrink\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3)) and ((resist or photoresist or imag\$3 or pattern\$3)) and ((fresist or or photoresist or imag\$3 or pattern\$3) and (fluorine or fluoride or "F" or "F. sub.2") and (hydrogen or "H" or "H. sub.2")))))) and (((imil1\$3 or ion adj beam or FTB or RIE or ion adj etch\$3 or sputter\$3) or elift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or imag\$3 or pattern\$3)) and ((heat\$3 or bak\$3) with (resist or photoresist or imag\$3 or pattern\$3))			or (GMR same magneto\$15)).ti,ab.) and		
treat\$4\ or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4\) same (resist or photoresist or imag\$3 or pattern\$3))\) and ((resist or photoresist or imag\$3 or pattern\$3)\) and ((resist or photoresist or imag\$3 or pattern\$3)\) and (fluorine or "I" or "O.sub.2")\) and (fluorine or "H" or "N.sub.2")\) and (hydrogen or "H" or "N.sub.2")\) and (hydrogen or "H" or "H.sub.2")\))))\) and ((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3\) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)\) near5 (resist or photoresist or imag\$3 or pattern\$3\))\) and ((heat\$3 or bax\$3)\) with (resist or photoresist or imag\$3 or pattern\$3\))\) and ((heat\$3 or bax\$3)\) with (resist or photoresist or imag\$3 or pattern\$3\))\) or (GMR same magneto\$15\)).ti,ab.) and (resist or photoresistive or magnetophotoresistive or photoplymer\$7\) or photoimag\$5\)) and ((ash\$3 or (ash adj treat\$4\) or etch\$3 or narrow\$3 or shrink\$3\) or shrink\$3\) or reduc\$3 or decreas\$3 or slim\$4\) or trim\$4 or less\$5 or tigh\$4\)) same (resist or photoresist or imag\$3 or pattern\$3\))\) and ((resist or photoresist or sima\$4\) or less\$5 or tigh\$4\) same (resist or photoresist or imag\$3 or pattern\$3\))\) and ((full\$3 or or (fullorine or "I" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (fluorine or "H" or "R.sub.2" or (nitrogen or "M" or "N.sub.2") and (fluorine or "H" or "R.sub.2" or (nitrogen or "H" or "R.sub.2" or or adj etch\$3 or jounter\$3\) or sputter\$3\) or clift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or			(resist or photoresist or photopolymer\$7		
treat\$4\ or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4\) same (resist or photoresist or imag\$3 or pattern\$3))\) and ((resist or photoresist or imag\$3 or pattern\$3)\) and ((resist or photoresist or imag\$3 or pattern\$3)\) and (fluorine or "I" or "O.sub.2")\) and (fluorine or "H" or "N.sub.2")\) and (hydrogen or "H" or "N.sub.2")\) and (hydrogen or "H" or "H.sub.2")\))))\) and ((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3\) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)\) near5 (resist or photoresist or imag\$3 or pattern\$3\))\) and ((heat\$3 or bax\$3)\) with (resist or photoresist or imag\$3 or pattern\$3\))\) and ((heat\$3 or bax\$3)\) with (resist or photoresist or imag\$3 or pattern\$3\))\) or (GMR same magneto\$15\)).ti,ab.) and (resist or photoresistive or magnetophotoresistive or photoplymer\$7\) or photoimag\$5\)) and ((ash\$3 or (ash adj treat\$4\) or etch\$3 or narrow\$3 or shrink\$3\) or shrink\$3\) or reduc\$3 or decreas\$3 or slim\$4\) or trim\$4 or less\$5 or tigh\$4\)) same (resist or photoresist or imag\$3 or pattern\$3\))\) and ((resist or photoresist or sima\$4\) or less\$5 or tigh\$4\) same (resist or photoresist or imag\$3 or pattern\$3\))\) and ((full\$3 or or (fullorine or "I" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (fluorine or "H" or "R.sub.2" or (nitrogen or "M" or "N.sub.2") and (fluorine or "H" or "R.sub.2" or (nitrogen or "H" or "R.sub.2" or or adj etch\$3 or jounter\$3\) or sputter\$3\) or clift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or			or photoimag\$5)) and ((ash\$3 or (ash adj		i
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or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or			magnetophotoresistive or (magneto adj	EPO; JPO;	
or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or			photoresistive) or (giant adj magneto\$15)	IBM TDB	
<pre>(resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or</pre>				_	į
or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3)) and ((resist or photoresist or imag\$3 or or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or			1 ' ' ' ' ' ' ' ' ' ' ' ' ' ' ' ' ' ' '		
treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or			, ,		
or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or			_		
littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or					
or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or					•
<pre>(resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or</pre>					
pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or					
or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or					
"O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or	1		pacternas; or nattornes; game //ovugon or		
fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or	}				
or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or	1				
or "H.sub.2")))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or					
adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or					
or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or					
or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or	1		adj beam or FIB or RIE or ion adj etch\$3		
back)) near5 (resist or photoresist or					]
	1			1	
imag\$3 or pattern\$3))					
1 1 2 1 2 1 2 1 2 1 2 1 2 1 2 1 2 1 2 1			imag\$3 or pattern\$3))		

_	33	(((((((magnetic adj head) or (magneto adj	USPAT;	2003/09/03 12:43
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
			ł .	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	1
		or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7		
	-	or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		ļ
	1	pattern\$3))) and ((resist or photoresist		
		1 2		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or	,	
		fluoride or "F" or "F.sub.2" or ((nitrogen	1	
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and (((mill\$3 or ion	:	
		adj beam or FIB or RIE or ion adj etch\$3		
		or sputter\$3) or (lift adj off or liftoff		
		or remov\$3 or etchback or etch\$3 adj		
		back)) near5 (resist or photoresist or		
		imag\$3 or pattern\$3))) not		
		((((((((magnetic adj head) or (magneto adj		
		resistive) or magnetoresistive or		
		magnetophotoresistive or (magneto adj		
		photoresistive) or (giant adj magneto\$15)	}	
	1	or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj	•	
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
	Ì	or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or	1	
		fluoride or "F" or "F.sub.2" or ((nitrogen	1	
		or "N" or "N.sub.2") and (hydrogen or "H"	1	
		or "H.sub.2")))))) and (((mill\$3 or ion		
		adj beam or FIB or RIE or ion adj etch\$3		
		or sputter\$3) or (lift adj off or liftoff		,
		or remov\$3 or etchback or etch\$3 adj		
		back)) near5 (resist or photoresist or	1	
		imag\$3 or pattern\$3))) and ((heat\$3 or		
		bak\$3) with (resist or photoresist or		· ·
		imag\$3 or pattern\$3)))	]	
			d	L

- 9	((((((magnetic adj head) or (magneto adj	USPAT;	2003/09/03 12:54
	resistive) or magnetoresistive or	US-PGPUB;	
!	magnetophotoresistive or (magneto adj	EPO; JPO;	
	photoresistive) or (giant adj magneto\$15)	IBM_TDB	
ļ .	or (GMR same magneto\$15)).ti,ab.) and		
!	(resist or photoresist or photopolymer\$7		
	or photoimag\$5)) and ((ash\$3 or (ash adj		
	treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
	or shrunk\$3 or contract\$3 or small\$3 or		
	littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
	or trim\$4 or less\$5 or tight\$4) same		
	(resist or photoresist or imag\$3 or		
	pattern\$3))) and ((resist or photoresist	į.	
	or imag\$3 or pattern\$3) same ((oxygen or		
	"O" or "O.sub.2") and (fluorine or		
	fluoride or "F" or "F.sub.2" or ((nitrogen		
	or "N" or "N.sub.2") and (hydrogen or "H"		
	or "H.sub.2"))))) not ((((((magnetic adj		
	head) or (magneto adj resistive) or		
	magnetoresistive or magnetophotoresistive		
	or (magneto adj photoresistive) or (giant		
	adj magneto\$15) or (GMR same		
	magneto\$15)).ti,ab.) and (resist or		
	photoresist or photopolymer\$7 or		
'	photoimag\$5)) and ((ash\$3 or (ash adj		
	treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
	or shrunk\$3 or contract\$3 or small\$3 or		3
	littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
	or trim\$4 or less\$5 or tight\$4) same		
	(resist or photoresist or imag\$3 or		
	<pre>pattern\$3))) and ((resist or photoresist</pre>		
	or imag\$3 or pattern\$3) same ((oxygen or		
	"O" or "O.sub.2") and (fluorine or		
	fluoride or "F" or "F.sub.2" or ((nitrogen		
	or "N" or "N.sub.2") and (hydrogen or "H"		
	or "H.sub.2")))))) and (((mill\$3 or ion		
	adj beam or FIB or RIE or ion adj etch\$3		
	or sputter\$3) or (lift adj off or liftoff		
	or remov\$3 or etchback or etch\$3 adj		
	back)) near5 (resist or photoresist or		
	imag\$3 or pattern\$3)))		

	1938	resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) not (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3))) and (fluorine or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/03/18 16:14
-	1 2	(("((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) not (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3)) and (fluorine or "O" or "O.sub.2") and (fluorine or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))) and (polymethylglutarimide)	USPAT; US-PGPUB USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/03/08 15:24 2003/09/03 13:04

				1 0 0 0 0 10 0 10 1
-	0	(((((magnetic adj head) or (magneto adj	USPAT;	2003/09/03 13:14
		resistive) or magnetoresistive or	US-PGPUB;	
1		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	
		or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		<pre>pattern\$3))) not (((((magnetic adj head)</pre>		
		or (magneto adj resistive) or		
		magnetoresistive or magnetophotoresistive		i i
		or (magneto adj photoresistive) or (giant		
		adj magneto\$15) or (GMR same		
		magneto\$15)).ti,ab.) and (resist or		
		photoresist or photopolymer\$7 or		
		photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and		
		(napthoquinonediazide or		
		napthoquinonediazido)		
_	51	1	USPAT;	2003/09/03 13:20
		(napthoguinonediazide or	US-PGPUB;	
		napthoquinonediazido)	EPO; JPO;	
		• •	IBM TDB	
_	3	((resist or photoresist) and	USPAT;	2003/09/03 13:25
		(napthoquinonediazide or	US-PGPUB;	
		napthoquinonediazido)) and (novolac or	EPO; JPO;	
		novolak) and dissolution near3 accelerat\$3	IBM_TDB	
<b> </b> -	5	("4524121"   "4745042"   "5252831"	USPAT	2003/03/10 09:27
		"5604073"   "5800963").PN.		
-	45	(430/314,316,319-320,328-329).ccls. and	USPAT;	2003/03/10 15:51
		((oxygen or "O.sub.2") same ((nitrogen or	US-PGPUB;	
		"N.sub.2") and (hydrogen or "H.sub.2"))	EPO; JPO;	
		same (ash\$3 or etch\$3))	IBM_TDB	0000/00/00 10 55
-	25	((430/314,316,319-320,328-329).ccls. and	USPAT;	2003/09/03 13:26
		((oxygen or "O.sub.2") same ((nitrogen or	US-PGPUB;	İ
		"N.sub.2") and (hydrogen or "H.sub.2"))	EPO; JPO;	
		same (ash\$3 or etch\$3))) and (heat\$3 or	IBM_TDB	
	216	bak\$3) same (resist or photoresist)	HCDAT.	2003/03/10 17:38
-	216	430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3)	USPAT;	2003/03/10 17:38
		(exposas) same (developas)	US-PGPUB; EPO; JPO;	
			IBM TDB	
	211	(430/328.ccls. and (heat\$3 or bak\$3) same	USPAT;	2003/09/03 13:31
	211	(expos\$3) same (develop\$3)) not	US-PGPUB;	2003/03/03 13.31
		(((430/314,316,319-320,328-329).ccls. and	EPO; JPO;	
		((oxygen or "O.sub.2") same ((nitrogen or	IBM TDB	
]	l	"N.sub.2") and (hydrogen or "H.sub.2"))		
		same (ash\$3 or etch\$3))) and (heat\$3 or		
		bak\$3) same (resist or photoresist))		
_	3	("2922855").PN.	USPAT;	2003/03/18 16:22
			US-PGPUB;	, 50, 20 20, 22
			JPO;	
			DERWENT	
				t